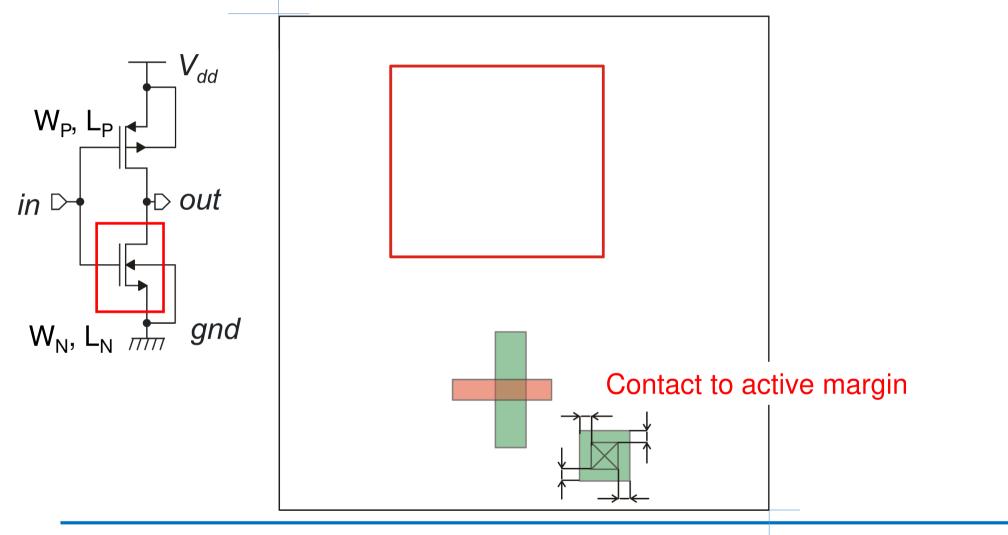
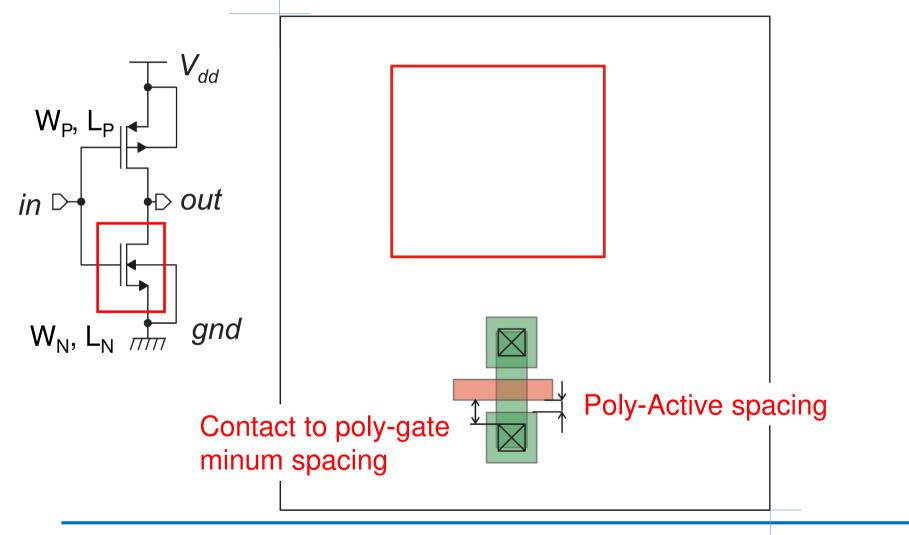


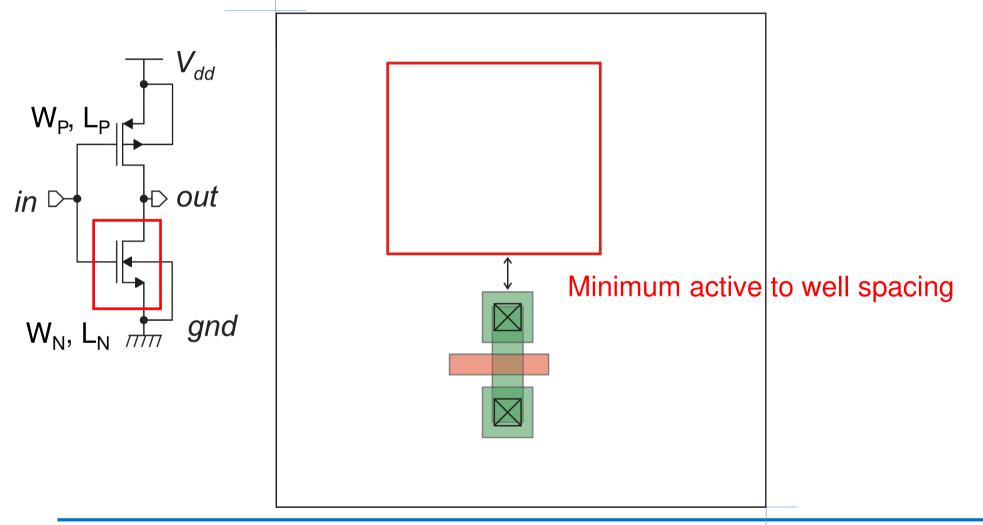
Then, we provide enough active surround to the contact



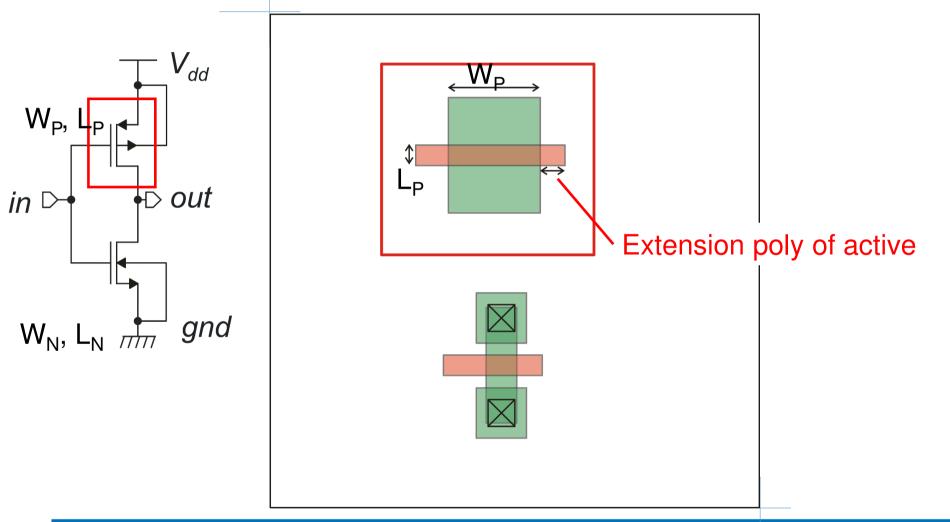
Then, we provide enough active surround to the contact

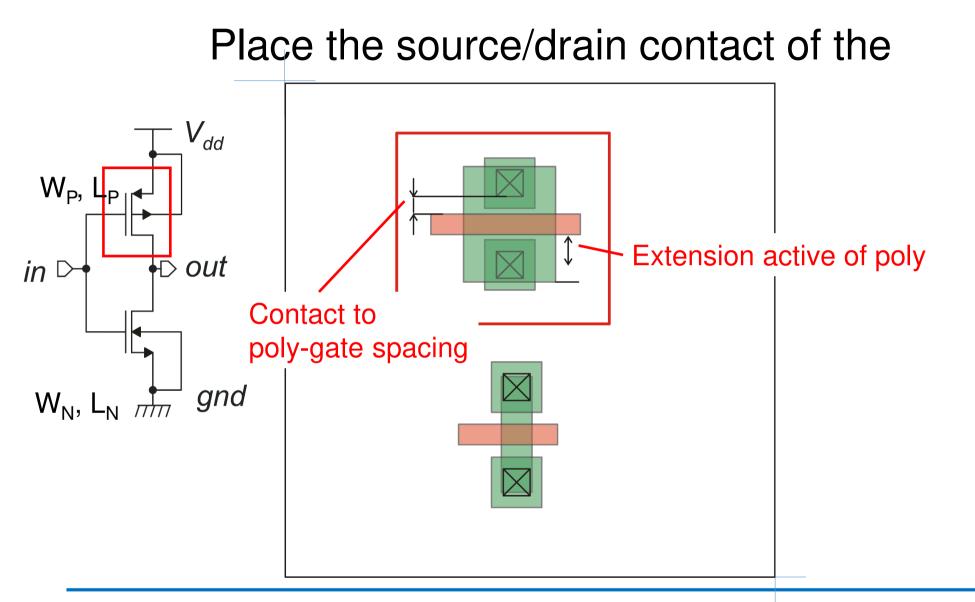


Place the n-MOS as close as possible to the n-well

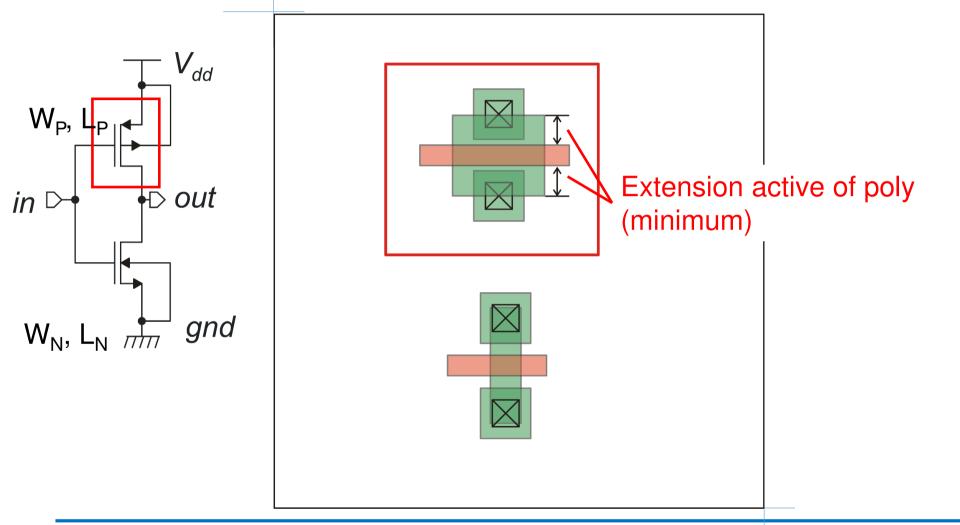


Now draw the p-MOS inside the n-well

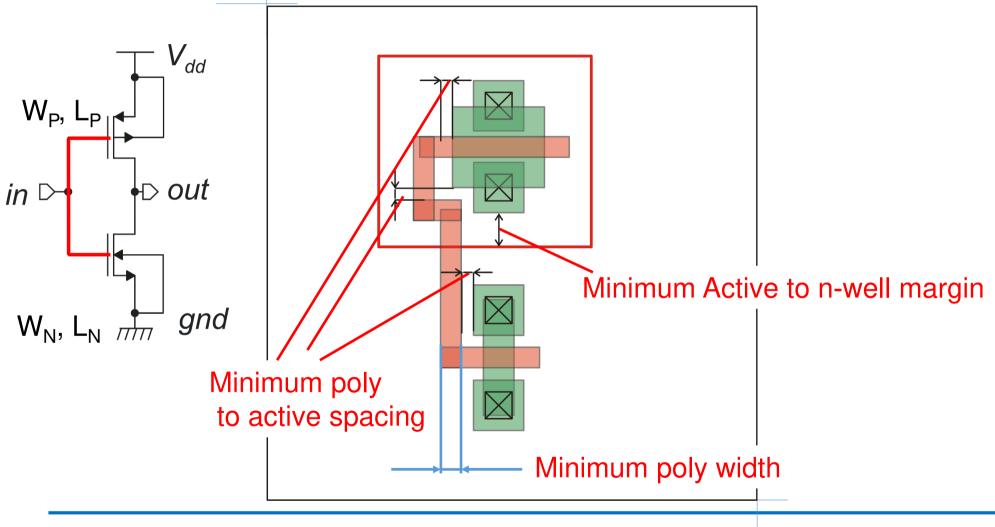


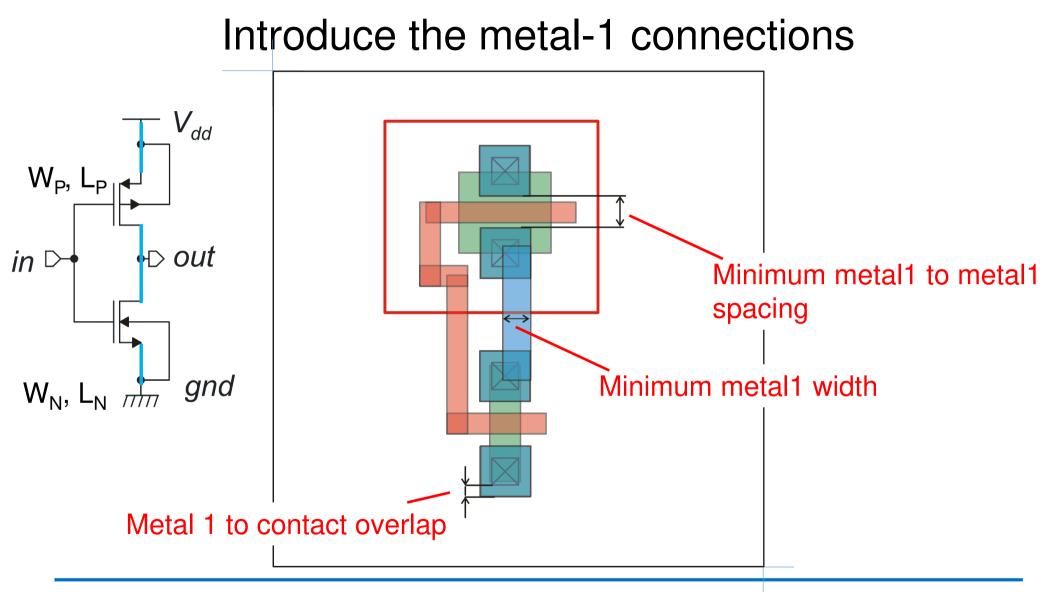


Reduce the active extension to the minimum

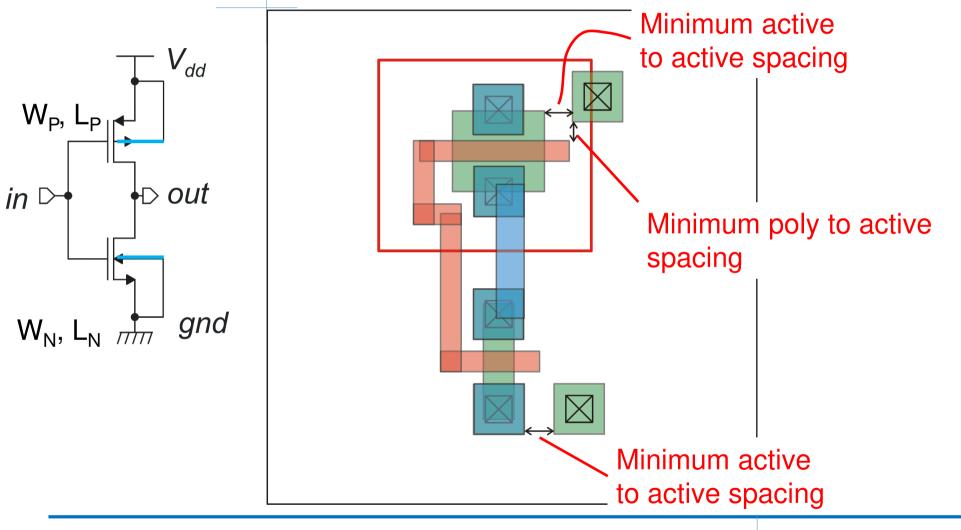


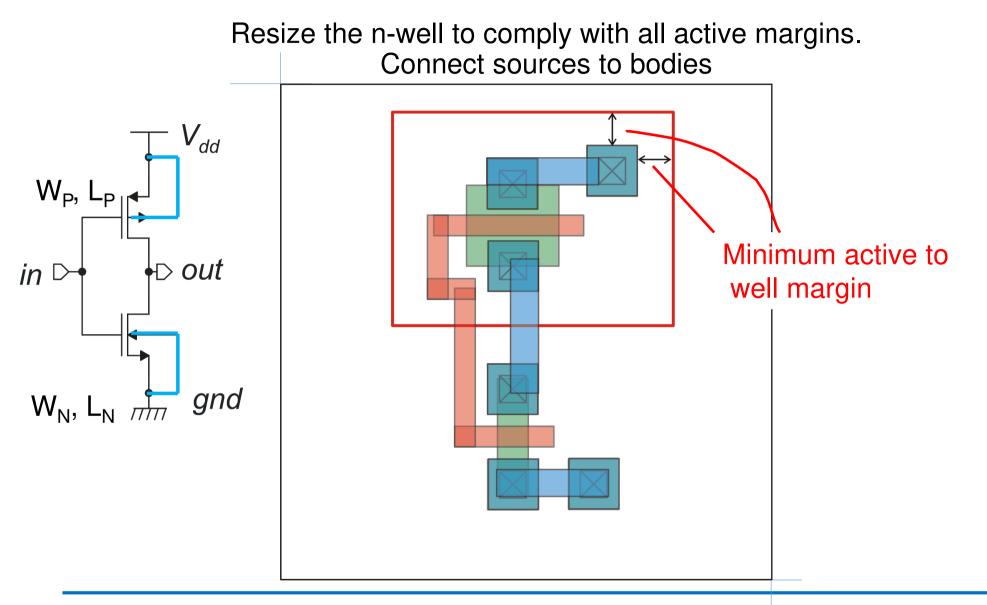
Connect the gates of the n-MOS and p-MOS



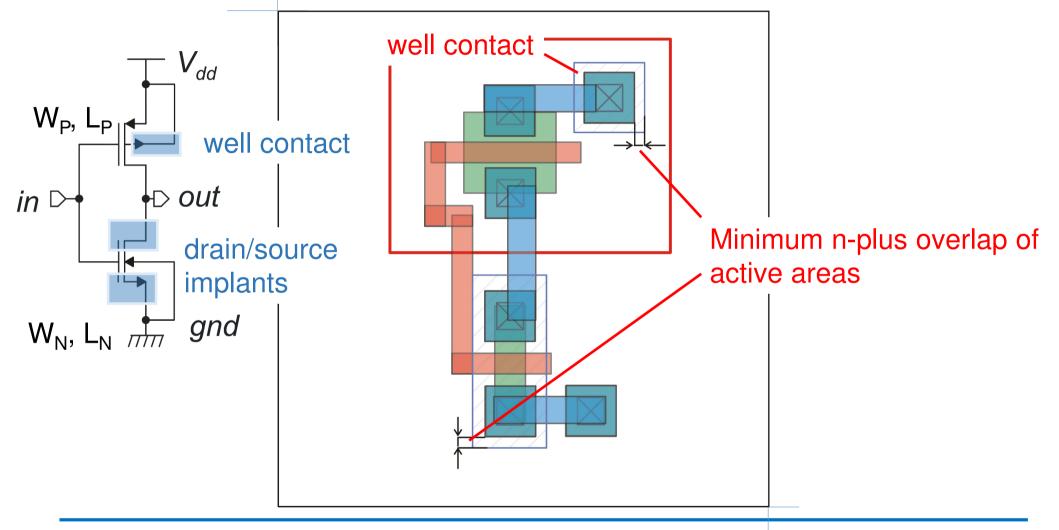


Introduce the substrate and n-well contacts

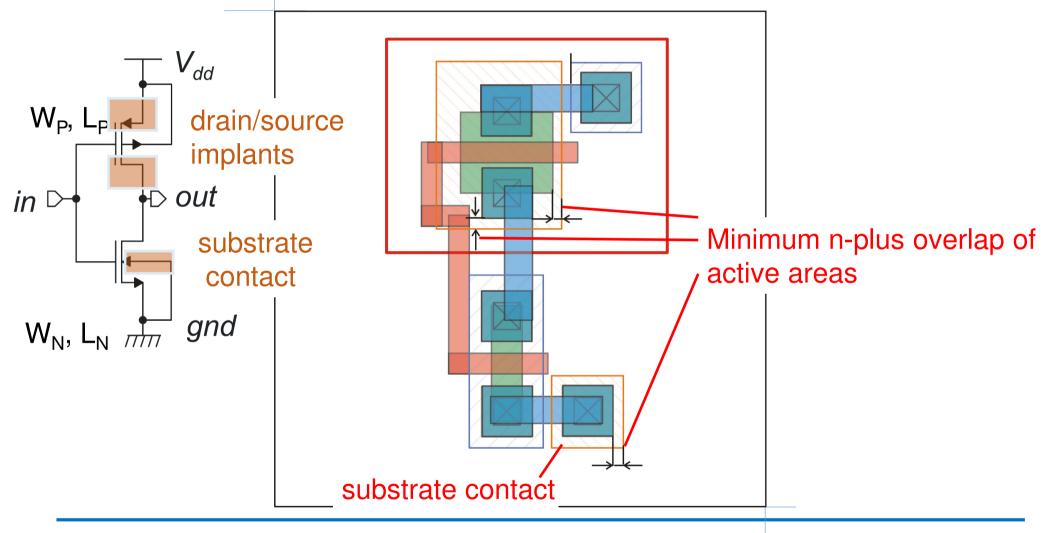




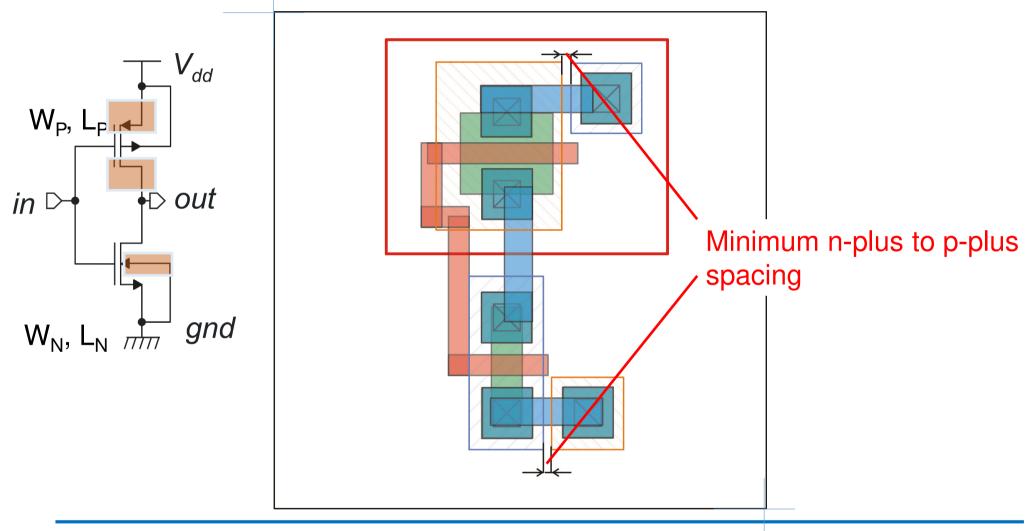
Cover all n-plus active areas with n-plus implant

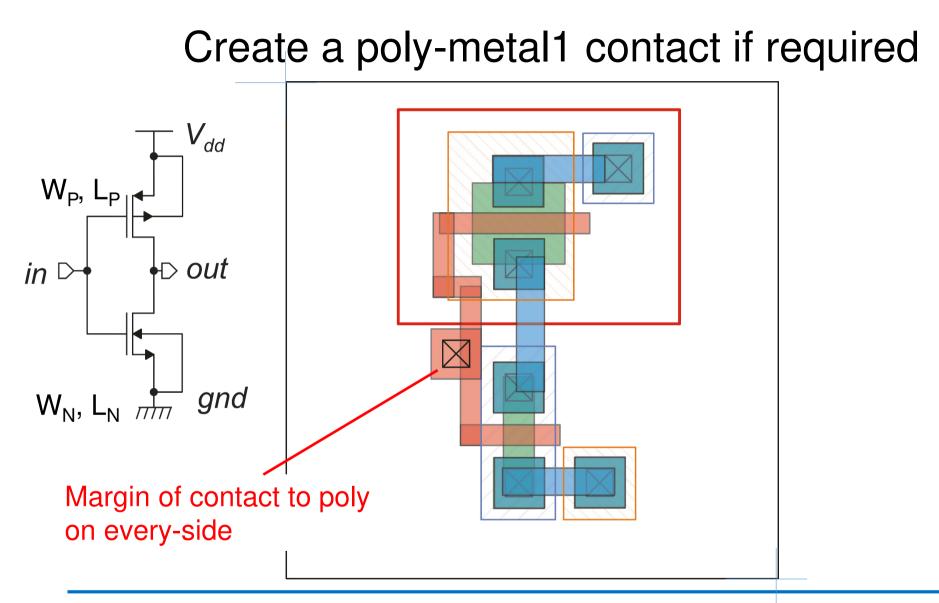


Same thing with p-plus active areas (p-plus implant)



Same thing with p-plus active areas (p-plus implant)





Create a poly-metal1 contact if required

